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PTO/SBr08a/b (08-03)
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S	ubstitute for form 1449A/B/F	πο		Complete if Known			
		_		Application Number 10/817,527			
	NFORMATIO	N DI	SCLOSURE	Filing Date	April 1, 2004		
	STATEMENT	BY /	APPLICANT	First Named Inventor	Daniel Krahmer, et al.		
l				Art Unit	N/A 2872		
	(Use as many sheets as necessary)			Examiner Name	Not Yet Assigned JUBA		
Shee	1	of	2	Attorney Docket Number	01641/100M577-US1		

U.S. PATENT DOCUMENTS							
Fuentas		Document Number	Publication Data	Name of Patentee or	Pages, Columns, Lines, Where		
Examiner Initials*	Cite No. ¹	Number-Kind Code ² (#known)		Applicant of Cited Document	Relevant Passages or Relevant Figures Appear		
THIS .	AA**	US-2003/0011896-A1	01-16-2003	Shiraishi	(
47	AB**	US-2003/0011893-A1	01-16-2003	Shiraishi et al.			
AP.	AC**	US-2003/0000453-A1	01-02-2003	Unno et al.			
44	AD**	US-2003/0012724-A1	01-16-2003	Burnett et al.			
-KK	AE**	US-2003/0021026-A1	01-30-2003	Allan et al.			
44	AF**	US-2003/0053036-A1	03-20-2003	Fujishima et al.			
2	AG**	US-2003/0058421-A1	03-27-2003	Omura et al.			
44	AH**	US-6,201,634-B1	03-13-2001	Sakuma et al.)		
AK.	Al**	US-6,324,003-B1	11-27-2001	Martin			

[&]quot; Pursuant to the Notice issued by the United States Patent and Trademark Office dated July 11, 2003 waiving the requirements of 37 C.F.R. § 1.98(a)(2)(i), a copy/copies of the United States Patent on PTO/SB08 is/are not being submitted.

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Evaminas	Cite	Foreign Patent Document	Publication	Name of Patentee or	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear					
Examiner Initials*,	No.1	Country Code ³ -Number ⁴ -Kind Code ⁶ (# known)	MM-DD-YYYY	Applicant of Cited Document						
-32	BA WO-01/01182-A1		01-04-2001	Corning Incorporated	<u> </u>					
***	BB	WO-01/50171-A1	07-12-2001	Carl Zeiss		\mathcal{I}				
86	ВС	WO-02/093209-A2	11-21-2002	Carl Zeiss Semiconductor Manufacturing Technologies AG	}	$\left[\right]$				
DA.	BD	WO-02/099500-A2	12-12-2002	Optical Research Associates	\	\Box				
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AX.	BF	WO-03/023481-A1	03-20-2003	Nikon Corporation		Π				
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-	вн	DE-40 22 904-A1	01-23-1992	Siemens AG	7	Π7				

EXAMINER: initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. "CITE NO.: Those patent(s) or publication(s) which are marked with an double asterisk (") next to the Cite No. are not supplied because they were previously cited by or submitted to the Office in a prior application relied upon in this application for an earlier filing date under 35 U.S.C. 120. 'Applicant's unique citation designation number (optional). 'See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. 'Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). 'For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. 'Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. Applicant is to place a check mark here if English language Translation is attached.

	NON PATENT LITERATURE DOCUMENTS						
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T	2			
Th	CA	Burnett, J.H., et al., "Intrinsic birefringence in calcium fluoride and barium fluoride", Physical Review B, Vol. 64, No. 24, December 15, 2001, pp. 241102-1 - 241102-4, XP-002218846.		\lceil			
75	СВ	Pastmak, J, et al., "Optical anisotropy of Silicon Single Crystals", Physical Review B (Solid State), April 15, 1971, Vol. 3, No. 8, pp. 2567-2571, XP-001109107.		Γ			
-61	CC	Van Peski, Chris; Memo to PAG Members, "Re: Birefringence of calcium fluoride", May 7, 2001, XP-002218847.	-	Γ			
78	ÇD	Van Peski, Chris; Memo to Exposure Tool Manufactures and Lens Designers, "Re: Birefringence of Calcium Fluoride", May 7, 2001, XP-002218848.		5			

Examiner Signature	John July	Date Considered II APRIL 2005	
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PTO/SB/08a/b (08-03)
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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Sheet 2 of 2

<u> </u>	Complete If Known					
Application Number	Application Number 10/817,527					
Filing Date	April 1, 2004					
First Named Inventor	Daniel Krahmer, et al.					
Art Unit	N/A	2872				
Examiner Name	Not Yet Assigned	JUBA				
Attorney Docket Number	01641/100M577-US1					

385	CE	Burnett, J.H., et al., "Intrinsic Birefringence in 157nm Materials" at 2nd International Symposium on 157nm Lithography in Dana Point, California, May 15, 2001, XP-002218849.)
88	CF	Burnett, J.H., et al., "Symmetry of spatial-dispersion-induced birefringence and its implications for CaF2 ultraviolet optics", J. Microlith., Microfab., Micosyste., Vol. 1, no. 3, October 3, 2002, pp. 213-224.	
4	CG	Relation between US20030011893 A1, US20030011896 A1 and WO 02093209.	3
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^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

^{&#}x27;Applicant's unique citation designation number (optional). ²Applicant is to place a check mark here if English language Translation is attached.

Sheet	1	of	3

Substitute Foon PTO-1449

U.S. Department of Commerce Patent and Trademark Office Attorney's Docket No. 17979-006002

Application No. 10/817,527

Information Disclosure Statement by Applicant (Use several sheets if necessary) Applicant
Daniel Krahmer et al.

Filing Date

Group Art Unit

(37 CFR §1.98(b))

April 1, 2004

2872

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Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
7/	AA	6,201,634	03/13/01	Sakuma et al.	\	4	(
177	AB	6,324,003	11/27/01	Martin)	
70	AC	US 2003- 0000453	01/02/03	Unno et al.			
数	AD	US 2003- 0012724	01/16/03	Burnett et al.			
1 7	AE	US 2003- 0011893	01/16/03	Shiraishi et al.			
· 10	AF	US 20030011896	01/16/03	Shiraishi			·
790	AG	US 2003- 0021026	01/30/03	Allan et al.			
-87	AH	US 20030025894	02/06/03	Owa et al.			
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-60	AK	US 2003/0086071	05/08/03	McGuire, Jr.			
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20	AT	US 2004/0036971	02/26/04	McGuire, Jr.			
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76	AV	US 2004/0145806	07/29/04	McGuire, Jr.			

Examiner Signature Jahn Luha	Date Considered
EXAMINER: Initials citation considered. Draw line thronext communication to applicant.	ough citation if not in conformance and not considered. Include copy of this form with

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 17979-006002	Application No. 10/817,527		
	closure Statement pplicant	Applicant Daniel Krahmer et al.			
(Use several s (37 CFR §1.98(b))	heets if necessary)	Filing Date April 1, 2004	Group Art Unit 2872		

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Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
TDD	AW	6,775,063	08/10/04	Shiraishi			

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Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation Yes No.	
-41	AX	DE 40 22 904	01/23/92	Germany			ABS,	
-10	AY	JP 11-106296	04/20/99	Japan			ABS,	
947	AZ	WO 01/01182	01/04/01	WIPO				
70	AAA	WO 01/50171	07/12/01	WIPO			ABS.	
D	ABB	WO 02/093209	11/21/02	WIPO			ABS.	
250	ACC	WO 02/097508	12/05/02	WIPO			ABS.	
<i>1</i> 38	ADD	WO 02/099500	12/12/02	WIPO				
H	AEE	WO 03/009017	01/30/03	WIPO			ABS.	
#	AFF	WO 03/023481	03/20/03	WIPO			ABS.	
*1	AGG	WO 03/038479	05/08/03	WIPO	2			
787	АНН	WO 03/046634	06/05/03	WIPO			A 85	
1575	AII	WO 04/019077	03/04/04	WIPO				

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Initial	ID	Document
36	AJJ	Burnett et al. "Intrinsic Birefringence in 157 nm Materials." 2 nd International Symposium on 157 nm Lithography in Dana Point, CA, May 15, 2001.
#	AKK	Burnett et al. "Intrinsic Birefringence in Calcium Fluoride and Barium Fluoride." Physical Review, B. Condensed Matter, American Institute of Physics. New York, US, Bd. 64, Nr. 24, pgs. 241102-1-241102-4, XP002218846, December 15, 2001.
750	ALL	Pastrnak et al. "Optical Anisotropy of Silicon Single Crystals." Physical Review B (Solid State). US, Bd. 3, Nr. 8, pgs. 2567-2571, XP-001109107, April 15, 1971.
39	AMM	Van Peski. Memo to Exposure Tool Manufactures and Lens Designers re: Birefringence of Calcium Fluoride." XP-002218848, May 7, 2001.

Examiner Signature Falm Luli-	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if no	t in conformance and not considered. Include copy of this form with
next communication to applicant.	

Substitute Disclosure Form (PTO-1449)

Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office				
1	closure Statement pplicant	Applicant Daniel Krahmer et al.			
(Use several sheets if necessary) (37 CFR §1.98(b))		Filing Date April 1, 2004	Group Art Unit 2872		

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-81	ANN	Van Peski. Memo to PAG Members re: Birefringence of Calcium Fluoride." XS-002218847, May 7, 2001.					

Examiner Signature Date Considered

11 APRIL 2005

EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Substitute Form PTO-1449 (Modified)

(37 CFR §1.98(b))

U.S. Department of Commerce Patent and Trademark Office

Attorney's Docket No. 17979-006002

Application No. 10/817,527

Information Disclosure Statement by Applicant (Use several sheets if necessary)

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8/24/2004

Applicant Daniel Krahmer et al.

Filing Date April 1, 2004 **Group Art Unit**

2872

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Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
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10	AB	1,332,410	3/2/1920	Potts Oscero W.			<u> </u>
12	AC	20040136084	07/15/2004	Unno et al.			
- 00 -	AD	20040050318	03/18/2004	Sakai, Keita			
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74	AG	6,765,717	07/20/2004	Allan et al.		1_/_	
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Hiraiwa et al.

Omura

Sakuma

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Examiner Initial	Desig.	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Trans Yes	lation No
%	AO.	EP0103485	3/21/1984	Europe)		
	AP	EP0857985	8/12/1998	Europe	. })		<u> X</u>
	AQ	EP1063551	12/27/0000	Europe				X
1	AR	DE19807120	8/26/1999	Germany			,	X
90	AS	JP09166710	6/24/1997	Japan	11		х	
	AT	JP2001108801	4/20/2001	Japan	_		abstrt	
700	AU	JP2000331927	11/30/2000	Japan			abstrt	
- ZB	AV	WO91/14189	9/19/1991	WIPO			AB'S.	
- 60 - 23	AW	WO00/70407	11/23/2000	WIPO			ABS	
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Examiner Signature	Date Considered
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EXAMINER: Initials citation considered. Draw line through citation if no	t in conformance and not considered. Include copy of this form with

next communication to applicant.

Application No. Attorney's Docket No. U.S. Department of Commerce Substitute Form PTO-1449 (Modified) 10/817,527 Patent and Trademark Office 17979-006002 Applicant Information Disclosure Statement Daniel Krahmer et al. by Applicant (Use several sheets if necessary) Group Art Unit Filing Date 2872 April 1, 2004 (37 CFR §1.98(b))

	Foreig	n Patent Doc	uments or P	ublished Foreign	Patent A	Application	ns	
Examiner Initial	Desig.	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Trans Yes	lation No
-74	AY	WO03/003072	1/9/2003	WIPO)	<u> </u>		
Ph	AZ	WO03/003429	1/9/2003	WIPO	}	\	ABS.	
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	Other Documents (include Author, Title, Date, and Place of Publication)					
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A	ABB	Burnett, J. H. et al., "Intrinsic Birefringence in calcium fluoride" Preprint handed out at 2 nd International Symposium on 157nm Lithography in Dana Point, California, May 15, 2001				
13b	ACC	Mulkens, J. et al. "157-nm technology: Where are we today?" Optical Microlithography XV. 2002. Vol. 4691, 613-625. Proceedings of the SPIE-Int. Soc. Opt. Eng., Santa Clara, CA, US, March 5-8 2002				
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Examiner Signature

Date Considered

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EXAMINER: Initials dilation considered. Draw line through dilation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Substitute Disclosure Form (PTO-1449)

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Sheet	1	of	À

Substitute Form PTO-1449

U.S. Department of Commerce Patent and Trademark Office Attorney's Docket No. 17979-006002

Application No. 10/817,527

Information Disclosure Statement by Applicant (Use several sheets if necessary) Applicant Krahmer et al.

Krahmer et al.
Filing Date

April 1, 2004

Group Art Unit 2872

(37 CFR §1.93(5))

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Examiner Initial	Desig. ID	Document Number	. Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate	
12	AA	6,785,051	8/31/04	Allan	_		7-15-02	

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Examiner	Desig.	Document	Publication	Country or			Trans	slation	
Initial	ID	Number	Date	Patent Office	Class	Subclass	Yes	No	
88	AB	WO 01/50171 (translation of abstract only)	07/12/01	WIPO	_		x		

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Examiner Signature your Tura	Date Considered I (APRIL 2005				
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered, include copy of this form with					
next communication to applicant.					